

IN THE CLAIMS:

Please CANCEL claims 1, 2 and 4-12 without prejudice to or disclaimer of the subject matter recited therein.

Please ADD new claims 13-25, as follows. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

1-12. (Canceled)

13. (New) A supporting apparatus for supporting a member which mounts a movable stage to a base, said apparatus comprising:

a first magnet arranged on one of the member and the base;

a second magnet unit arranged on the other of the member and the base on which said first magnet is arranged, and arranged so that said first magnet is interposed,

wherein magnetized directions of said first magnet and said second magnet unit are perpendicular to a supporting direction of the member, and

wherein a width size of said second magnet unit in a perpendicular direction to the magnetized directions and the supporting direction is larger than a width size of said first magnet.

14. (New) The apparatus according to claim 13, further comprising an electromagnetic actuator which is arranged between the member and the base, and provides a force which acts on the member.

15. (New) The apparatus according to claim 13, wherein said second magnet unit is arranged on the base.

16. (New) The apparatus according to claim 15, further comprising changing means for changing a region in which said first magnet and said second magnet unit face each other.

17. (New) The apparatus according to claim 16, wherein said changing means moves a plurality of magnets which constitute said second magnet unit in the perpendicular direction to the magnetized directions and the supporting direction.

18. (New) The apparatus according to claim 13, wherein said first magnet and said second magnet unit are arranged so that a spring constant becomes substantially zero in the perpendicular direction to the magnetized directions and the supporting direction.

19. (New) An exposure apparatus for exposing a pattern onto a substrate mounted on a stage, said apparatus comprising:

a supporting apparatus, as defined in claim 13, for supporting a member mounted the stage.

20. (New) A device manufacturing method comprising:

a step of exposing a pattern onto a substrate by using an exposure apparatus defined in claim 19; and

a step of developing the substrate.

21. (New) A supporting apparatus for supporting a member which mounts a movable stage to a base in a first direction, said supporting apparatus comprising:

a first magnet arranged on the member, and magnetized in a second direction perpendicular to the first direction;

a second magnet unit arranged on the base, and arranged so that said first magnet is interposed; and

moving means for moving a plurality of magnets which constitute said second magnet unit in a third direction perpendicular to the first direction and the second direction.

22. (New) The apparatus according to claim 21, wherein a supporting force for supporting the base is changed by using said moving means.

23. (New) The apparatus according to claim 22, wherein the supporting force is changed based on moving of the plurality of magnets corresponding to moving of the stage.

24. (New) An exposure apparatus for exposing a pattern onto a substrate mounted on a stage, said apparatus comprising:

a supporting apparatus, as defined in claim 21, for supporting a member mounted to the stage.

25. (New) A device manufacturing method comprising:

a step of exposing a pattern onto a substrate by using an exposure apparatus as defined in claim 24; and

a step of developing the substrate.